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ABSTRACT

A vertical JFET 1a according to the present invention has an n⁺ type drain semiconductor portion 2, an n-type drift semiconductor portion 3, a p⁺ type gate semiconductor portion 4, an n-type channel semiconductor portion 5, an n⁺ type source semiconductor portion 7, and a p⁺ type gate semiconductor portion 8. The n-type drift semiconductor portion 3 is placed on a principal surface of the n⁺ type drain semiconductor portion 2 and has first to fourth regions 3a to 3d extending in a direction intersecting with the principal surface. The p⁺ type gate semiconductor portion 4 is placed on the first to third regions 3a to 3c of the n-type drift semiconductor portion 3. The n-type channel semiconductor portion 5 is placed along the p⁺ type gate semiconductor portion 4 and is electrically connected to the fourth region 3d of the n-type drift semiconductor portion 3.